

Agenda Highlights - 2022 EUVL Workshop and Supplier Showcase

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We have an excellent agenda for the upcoming 2022 EUVL Workshop and Supplier Showcase, which begins on June 4th and runs through June 9th. As the final agenda was just recently published, I wanted to point out some of the agenda highlights to the community.

Keynote Presentations – Focus on High NA and Updates

With EUVL now in fabs, the industry's focus has shifted to the readiness of High - NA EUVL. I look forward to the keynote presentation from Kurt Ronse, of imec, on their joint High-NA EUV development with ASML. His talk will cover eco-system readiness and challenges; and will be followed by a keynote presentation from Jan van Schoot of ASML on the overview of the current state of the 0.33NA technology and readiness of the High-NA scanner. Additionally, Steve Carson of Intel will give an update on challenges and the outlook for Intel's future usage of High-NA EUVL.

In the Supplier Showcase, scheduled for Wednesday, June 8th, keynote speaker Ralph Dammel of EMD Electronics, will share his "Confessions of an EUV Skeptic" and speak to how certain obstacles of implementing EUVL into fabs were overcome. Mike Lercel, of ASML, another keynote speaker will present on EUVL infrastructure and progress in EUVL, which has enabled EUVL to be used in HVM fabs.

Quantum Computers are the leading contenders for computers beyond current silicon-based technology. In his keynote presentation, Paul Welander, of SLAC, will share the latest update on this fascinating technology.

Short Courses

The workshop will begin with two short courses on EUVL and Nanoimaging (June 4th and 5th).

Attendees interested in Nanoscale Imaging will find the short course “Advanced Photon Sources and Applications in Nanoscale Imaging” taught by David Attwood on June 4th, of much value.

If you want to get an in-depth overview of EUVL, don’t miss the EUVL short course on June 5th. Along with Patrick Naulleau, Jinho Ahn, and Jan van Schoot, I will also be lecturing.

More information, including a detailed brochure, about the short courses can be found on our website at <http://www.euvlitho.com/education>

Invited Presentations

With ~ 60 presentations scheduled for the workshop, it is difficult to pick favorites. However, here are some that caught my attention:

- Improvement of Patterning Performance in EUV Lithography (Jung Sik Kim, Hynix)
- ZEISS EUV Optics – Past, Present and Future (Simon Bihl, Zeiss)
- Progressing Insights on Low-n Masks for EUV Lithography (Claire van Lare, ASML)
- Characterization of 1- and 2-um Solid-State-Laser-Driven Plasma Sources of EUV Light (Oscar Versolato, ARCNL)
- Photoresist Roughness Understanding & LWR floor (Joost van Bree, ASML)
- EUV Resist Challenges and Chemical Stochastics (Greg Denbeaux, University of Albany)
- Advanced EUV Resist Patterning with Metal Oxide Resist (Seiji Nagahara, Tokyo Electron Limited)
- EUV Lensless Imaging with Synthetic Pupil Illumination (Iacopo Mochi, Paul Scherrer Institute)
- Aperiodic Multilayers as EUV Mask Mirrors (Marcelo Ackermann, University of Twente)

Supplier Showcase

This year we have combined the Supplier Showcase with the EUVL Workshop to bring awareness to companies and their products, services, and R&D that are making EUVL implementation and its continued extension possible. We will have presentations from several non-profit organizations that are EUVL focused such as CXRO, EUV-IUCC, Fraunhofer, IIT, PTB, TNO, the University of Albany, and the University of Hyogo. We will also hear from suppliers like Energetiq, IM, Molecular Vista, optiXfab, Rigaku, scia Systems, and Veeco. For additional presenters please see the agenda listed online at www.euvlitho.com.

LBNL Program Showcase

This year's workshop is being co-organized by CXRO / LBNL, with Patrick Naulleau as co-chair. Like in previous events, the EUVL Workshop includes a program showcase from the co-host organization. CXRO continues to be a leader in developing EUV technology to address current and future needs for EUVL manufacturing. In the showcase, there will be presentations on a new kind of "Beyond CMOS" microelectronics, new materials, and diagnostics programs that will enable the next generation of microelectronics. With a truly, world-class infrastructure and staff, the LBNL program showcase is a window into the world of tomorrow and is not to be missed!

Sponsor the 2022 Workshop and Gain EUVL Community Visibility

This workshop is a wonderful opportunity for suppliers to showcase their products and services to EUVL customers. Don't miss this chance for visibility from leading-edge chip makers, OEM and infrastructure suppliers, and distinguished attendees.

There are several sponsorship tiers to choose from and all tiers include at least ONE complementary registration. If you're interested in sponsoring you can visit [this page](#) for more information; and if you have any questions, please reach out to our Executive Assistant at jessica.pelle@euvlitho.com.

The Final Agenda and Abstract Book are available at our website www.euvlitho.com.

We are looking forward to a wonderful event and hope to see you there!